Luc Stafford

List of Publications by Year in Descending Order

136 papers	1,261 citations	17 h-index	25 g-index
148 ext. papers	1,496 ext. citations	3.3 avg, IF	4.68 L-index

#	Paper	IF	Citations
136	Refined analysis of current–voltage characteristics in Townsend dielectric barrier discharges in nitrogen at atmospheric pressure. *Journal Physics D: Applied Physics*, **2021**, 54, 095204	3	0
135	Ultra-high-resolution optical absorption spectroscopy of DC plasmas at low pressure using a supercontinuum laser combined with a laser line tunable filter and a HyperFine spectrometer. *Journal Physics D: Applied Physics*, **2021**, 54, 085204	3	1
134	TiO2–SiO2 nanocomposite thin films deposited by direct liquid injection of colloidal solution in an O2/HMDSO low-pressure plasma. *Journal Physics D: Applied Physics*, **2021**, 54, 085206	3	4
133	Plasma–graphene interactions: combined effects of positive ions, vacuum-ultraviolet photons, and metastable species. *Journal Physics D: Applied Physics*, **2021**, 54, 295202	3	1
132	Preferential self-healing at grain boundaries in plasma-treated graphene. *Nature Materials*, **2021**, 20, 49-54	27	16
131	Modification of microfibrillated cellulosic foams in a dielectric barrier discharge at atmospheric pressure. *Plasma Processes and Polymers*, **2021**, 18, 2000158	3.4	2
130	Response surface methodology as a predictive tool for the fabrication of coatings with optimal anti-fogging performance. *Thin Solid Films*, **2021**, 718, 138482	2.2	2
129	Incorporation-limiting mechanisms during nitrogenation of monolayer graphene films in nitrogen flowing afterglows. *Nanoscale*, **2021**, 13, 2891-2901	7.7	1
128	On the rotational–translational equilibrium in non-thermal argon plasmas at atmospheric pressure. *Plasma Sources Science and Technology*, **2021**, 30, 035020	3.5	2
127	Postgrowth modification of monolayer graphene films by low-pressure diborane-argon plasma. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2021**, 39, 043003	2.9	
126	Characterization of non-thermal dielectric barrier discharges at atmospheric pressure in presence of microfibrillated cellulosic foams. *Plasma Sources Science and Technology*, **2021**, 30, 095019	3.5	0
125	Selective nitrogen doping of graphene due to preferential healing of plasma-generated defects near grain boundaries. *Npj 2D Materials and Applications*, **2020**, 4,	8.8	5
124	Probing plasma-treated graphene using hyperspectral Raman. *Review of Scientific Instruments*, **2020**, 91, 063903	1.7	6
123	Unveiling the origin of the anti-fogging performance of plasma-coated glass: Role of the structure and the chemistry of siloxane precursors. *Progress in Organic Coatings*, **2020**, 141, 105401	4.8	6
122	Toward More Sustainable Rechargeable Aqueous Batteries Using Plasma-Treated Cellulose-Based Li-Ion Electrodes. *ACS Sustainable Chemistry and Engineering*, **2020**, 8, 4728-4733	8.3	7
121	Atmospheric pressure Townsend discharges as a promising tool for the one-step deposition of antifogging coatings from N2O/TMCTS mixtures. *Plasma Processes and Polymers*, **2020**, 17, 1900186	3.4	3
120	Deposition of anti-fog coatings on glass substrates using the jet of an open-to-air microwave argon plasma at atmospheric pressure. *Plasma Processes and Polymers*, **2020**, 17, 1900229	3.4	8

119	Spatio-temporal dynamics of a nanosecond pulsed microwave plasma ignited by time reversal. *Plasma Sources Science and Technology*, **2020**, 29, 125017	3.5	0
118	Time-resolved imaging of pulsed positive nanosecond discharge on water surface: plasma dots guided by water surface. *Plasma Sources Science and Technology*, **2020**, 29, 115017	3.5	2
117	Beyond microelectronics with 1,3,5,7-tetramethylcyclotetrasiloxane: A promising molecule for anti-fogging coatings. *Materials Chemistry and Physics*, **2020**, 242, 122508	4.4	4
116	Modification of the optical properties and nano-crystallinity of anatase TiO2nanoparticles thin film using low pressure O2 plasma treatment. *Thin Solid Films*, **2020**, 709, 138212	2.2	2
115	Multi-pass deposition of organosilicon-based superhydrophobic coatings in atmospheric pressure plasma jets. *Thin Solid Films*, **2020**, 714, 138369	2.2	3
114	Recent progress on organosilicon coatings deposited on bleached unrefined Kraft paper by non-thermal plasma process at atmospheric pressure. *Progress in Organic Coatings*, **2020**, 147, 105865	4.8	5
113	Analysis of transport phenomena during plasma deposition of hydrophobic coatings on porous cellulosic substrates in plane-to-plane dielectric barrier discharges at atmospheric pressure. *Plasma Processes and Polymers*, **2020**, 17, 2000091	3.4	5
112	Spatially-Resolved Spectroscopic Diagnostics of a Miniature RF Atmospheric Pressure Plasma Jet in Argon Open to Ambient Air. *Plasma*, **2020**, 3, 38-53	1.7	4
111	Emission and absorption diagnostics of a diffuse dielectric barrier discharge with multiple current peaks in helium at atmospheric pressure. *Plasma Sources Science and Technology*, **2019**, 28, 085011	3.5	3
110	Development of Organosilicon-Based Superhydrophobic Coatings through Atmospheric Pressure Plasma Polymerization of HMDSO in Nitrogen Plasma. *Materials*, **2019**, 12,	3.5	23
109	Multi-scale investigation in the frequency domain of Ar/HMDSO dusty plasma with pulsed injection of HMDSO. *Plasma Sources Science and Technology*, **2019**, 28,	3.5	6
108	Time and space-resolved experimental investigation of the electron energy distribution function of a helium capacitive discharge at atmospheric pressure. *Journal Physics D: Applied Physics*, **2019**, 52, 245202	3	2
107	Experiments and kinetic modeling of the ion energy distribution function at the substrate surface during magnetron sputtering of silver targets in radio frequency argon plasmas. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2019**, 37, 021301	2.9	5
106	Influence of N2, O2, and H2 admixtures on the electron power balance and neutral gas heating in microwave Ar plasmas at atmospheric pressure. *Journal Physics D: Applied Physics*, **2019**, 52, 475201	3	13
105	Time-resolved analysis of the precursor fragmentation kinetics in an hybrid PVD/PECVD dusty plasma with pulsed injection of HMDSO. *Plasma Processes and Polymers*, **2019**, 16, 1900044	3.4	3
104	Characterization of a microwave argon plasma column at atmospheric pressure by optical emission and absorption spectroscopy coupled with collisional-radiative modelling. *Physics of Plasmas*, **2019**, 26, 063516	2.1	13
103	A combination of plasma diagnostics and Raman spectroscopy to examine plasma-graphene interactions in low-pressure argon radiofrequency plasmas. *Journal of Applied Physics*, **2019**, 126, 233302	2.5	10
102	On the Icephobic Behavior of Organosilicon-Based Surface Structures Developed Through Atmospheric Pressure Plasma Deposition in Nitrogen Plasma. *Coatings*, **2019**, 9, 679	2.9	10

101	Low-damage nitrogen incorporation in graphene films by nitrogen plasma treatment: Effect of airborne contaminants. *Carbon*, **2019**, 144, 532-539	10.4	13
100	Highly porous micro-roughened structures developed on aluminum surface using the jet of rotating arc discharges at atmospheric pressure. *Journal of Applied Physics*, **2018**, 123, 073302	2.5	5
99	Electron density and temperature in an atmospheric-pressure helium diffuse dielectric barrier discharge from kHz to MHz. *Plasma Sources Science and Technology*, **2018**, 27, 035005	3.5	12
98	Time-resolved study of the electron temperature and number density of argon metastable atoms in argon-based dielectric barrier discharges. *Plasma Sources Science and Technology*, **2018**, 27, 015015	3.5	12
97	Interaction of N and O atoms with hardwood and softwood surfaces in the flowing afterglow of N2-O2 microwave plasmas. *Plasma Processes and Polymers*, **2018**, 15, e1800035	3.4	1
96	Analysis of the high-energy electron population in surface-wave plasma columns in presence of collisionless resonant absorption. *Plasma Sources Science and Technology*, **2018**, 27, 095011	3.5	3
95	Treatment of graphene films in the early and late afterglows of N2 plasmas: comparison of the defect generation and N-incorporation dynamics. *Plasma Sources Science and Technology*, **2018**, 27, 124004	3.5	8
94	Probing suprathermal electrons by trace rare gases optical emission spectroscopy in low pressure dipolar microwave plasmas excited at the electron cyclotron resonance. *Physics of Plasmas*, **2018**, 25, 093511	2.1	1
93	Influence of a square pulse voltage on argon-ethyl lactate discharges and their plasma-deposited coatings using time-resolved spectroscopy and surface characterization. *Physics of Plasmas*, **2018**, 25, 103504	2.1	4
92	Interaction of atomized colloid with an ac electric field in a dielectric barrier discharge reactor used for deposition of nanocomposite coatings. *Journal Physics D: Applied Physics*, **2017**, 50, 075201	3	15
91	In situ investigation of magnetron sputtering plasma used for the deposition of multiferroic BiFeO3 thin films. *Journal of Materials Science: Materials in Electronics*, **2017**, 28, 15749-15753	2.1	2
90	Enhancing the water repellency of wood surfaces by atmospheric pressure cold plasma deposition of fluorocarbon film. *RSC Advances*, **2017**, 7, 29159-29169	3.7	7
89	Influence of substrate outgassing on the plasma properties during wood treatment in He dielectric barrier discharges at atmospheric pressure. *Plasma Processes and Polymers*, **2017**, 14, 1600172	3.4	11
88	Characterization of argon dielectric barrier discharges applied to ethyl lactate plasma polymerization. *Journal Physics D: Applied Physics*, **2017**, 50, 475205	3	10
87	Deposition of fluorocarbon groups on wood surfaces using the jet of an atmospheric-pressure dielectric barrier discharge. *Wood Science and Technology*, **2017**, 51, 1339-1352	2.5	11
86	Deposition of nanocomposite coatings on wood using cold discharges at atmospheric pressure. *Surface and Coatings Technology*, **2017**, 309, 729-737	4.4	31
85	Nanoparticle synthesis by high-density plasma sustained in liquid organosilicon precursors. *Journal of Applied Physics*, **2017**, 122, 243301	2.5	3
84	Spectroscopic diagnostics of low-pressure inductively coupled Kr plasma using a collisional-radiative model with fully relativistic cross sections. *Plasma Sources Science and Technology*, **2016**, 25, 035025	3.5	13

83	Determination of the electron temperature in plane-to-plane He dielectric barrier discharges at atmospheric pressure. *Plasma Sources Science and Technology*, **2016**, 25, 015011	3.5	12
82	Nebulization of Nanocolloidal Suspensions for the Growth of Nanocomposite Coatings in Dielectric Barrier Discharges. *Plasma Processes and Polymers*, **2016**, 13, 981-989	3.4	24
81	Influence of the voltage waveform during nanocomposite layer deposition by aerosol-assisted atmospheric pressure Townsend discharge. *Journal of Applied Physics*, **2016**, 120, 053302	2.5	18
80	Deposition of TiO2-SiO2 nanocomposite coatings using atmospheric-pressure plasmas **2016**,		1
79	Determination of active species in the modification of hardwood samples in the flowing afterglow of N2 dielectric barrier discharges open to ambient air. *Cellulose*, **2015**, 22, 811-827	5.5	24
78	Determination of the number density of excited and ground Zn atoms during rf magnetron sputtering of ZnO target. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2015**, 33, 041302	2.9	3
77	Modification of hardwood samples in the flowing afterglow of N2O2 dielectric barrier discharges open to ambient air. *Cellulose*, **2015**, 22, 3397-3408	5.5	15
76	Surface free radicals detection using molecular scavenging method on black spruce wood treated with cold, atmospheric-pressure plasmas. *Applied Surface Science*, **2015**, 359, 137-142	6.7	11
75	Effect of extractives in plasma modification of wood surfaces. *Surface Innovations*, **2015**, 3, 196-205	1.9	8
74	Spatially resolved electron density and electron energy distribution function in Ar magnetron plasmas used for sputter-deposition of ZnO-based thin films. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2015**, 33, 061310	2.9	1
73	Cyclic evolution of the electron temperature and density in dusty low-pressure radio frequency plasmas with pulsed injection of hexamethyldisiloxane. *Applied Physics Letters*, **2015**, 107, 183104	3.4	11
72	Microstructural and optical properties tuning of BiFeO3 thin films elaborated by magnetron sputtering. *Journal of Materials Science: Materials in Electronics*, **2015**, 26, 3316-3323	2.1	5
71	Organization of Dielectric Barrier Discharges in the Presence of Structurally Inhomogeneous Wood Substrates. *IEEE Transactions on Plasma Science*, **2014**, 42, 2366-2367	1.3	4
70	Spatially Modulated Emission of ECR Plasmas in Helium. *IEEE Transactions on Plasma Science*, **2014**, 42, 2762-2763	1.3	2
69	Electrical characterization of the flowing afterglow of N2 and N2/O2 microwave plasmas at reduced pressure. *Journal of Applied Physics*, **2014**, 115, 163303	2.5	13
68	Optical emission spectroscopy of microwave-plasmas at atmospheric pressure applied to the growth of organosilicon and organotitanium nanopowders. *Journal of Applied Physics*, **2014**, 115, 113301	2.5	15
67	Effect of Wood Surface Modification by Atmospheric-Pressure Plasma on Waterborne Coating Adhesion. *BioResources*, **2014**, 9,	1.3	14
66	Evidence of local power deposition and electron heating by a standing electromagnetic wave in electron-cyclotron-resonance plasma. *Physical Review E*, **2014**, 90, 033106	2.4	5

65	Experimental and modelling study of organization phenomena in dielectric barrier discharges with structurally inhomogeneous wood substrates. *Plasma Sources Science and Technology*, **2014**, 23, 054006	3.5	8
64	Improvement of the emission properties from InGaN/GaN dot-in-a-wire nanostructures after treatment in the flowing afterglow of a microwave N□plasma. *Nanotechnology*, **2014**, 25, 435606	3.4	8
63	Improved water repellency of black spruce wood surfaces after treatment in carbon tetrafluoride plasmas. *Wood Science and Technology*, **2013**, 47, 411-422	2.5	40
62	Role of substrate outgassing on the formation dynamics of either hydrophilic or hydrophobic wood surfaces in atmospheric-pressure, organosilicon plasmas. *Surface and Coatings Technology*, **2013**, 234, 42-47	4.4	29
61	Measurements of sputtered neutrals and ions and investigation of their roles on the plasma properties during rf magnetron sputtering of Zn and ZnO targets. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2013**, 31, 061306	2.9	5
60	Emission spectra from direct current and microwave powered Hg lamps at very high pressure. *Journal Physics D: Applied Physics*, **2013**, 46, 455201	3	6
59	Deposition of Hydrophobic Functional Groups on Wood Surfaces Using Atmospheric-Pressure Dielectric Barrier Discharge in Helium-Hexamethyldisiloxane Gas Mixtures. *Plasma Processes and Polymers*, **2012**, 9, 1168-1175	3.4	55
58	Nonlocal effect of plasma resonances on the electron energy-distribution function in microwave plasma columns. *Physical Review E*, **2012**, 86, 015402	2.4	8
57	Populations of metastable and resonant argon atoms in radio frequency magnetron plasmas used for deposition of indium-zinc-oxide films. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2012**, 30, 021301	2.9	13
56	Characterization of a low-pressure chlorine plasma column sustained by propagating surface waves using phase-sensitive microwave interferometry and trace-rare-gas optical emission spectroscopy. *Journal of Applied Physics*, **2011**, 109, 113304	2.5	5
55	Critical review: Plasma-surface reactions and the spinning wall method. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2011**, 29, 010801	2.9	25
54	On the validity of neutral gas temperature by N2rovibrational spectroscopy in low-pressure inductively coupled plasmas. *Plasma Sources Science and Technology*, **2011**, 20, 035016	3.5	9
53	Simulation of redeposition during platinum etching in argon plasmas. *Journal of Applied Physics*, **2010**, 107, 063306	2.5	8
52	Experimental and modeling study of O and Cl atoms surface recombination reactions in O2 and Cl2 plasmas. *Pure and Applied Chemistry*, **2010**, 82, 1301-1315	2.1	14
51	Modification of Sugar Maple (Acer saccharum) and Black Spruce (Picea mariana) Wood Surfaces in a Dielectric Barrier Discharge (DBD) at Atmospheric Pressure. *Journal of Adhesion Science and Technology*, **2010**, 24, 1401-1413	2	47
50	Correlation between surface chemistry and ion energy dependence of the etch yield in multicomponent oxides etching. *Journal of Applied Physics*, **2009**, 106, 063302	2.5	3
49	Electron energy distribution functions in low-pressure oxygen plasma columns sustained by propagating surface waves. *Applied Physics Letters*, **2009**, 94, 021503	3.4	11
48	Effect of Cu contamination on recombination of O atoms on a plasma-oxidized silicon surface. *Journal of Applied Physics*, **2009**, 105, 113309	2.5	16

47	Recombination of chlorine atoms on plasma-conditioned stainless steel surfaces in the presence of adsorbed Cl2. *Journal Physics D: Applied Physics*, **2009**, 42, 055206	3	27
46	Aging and Stability of GaN High Electron Mobility Transistors and Light-Emitting Diodes With $\hbox{TiB}_{2}$- and Ir-Based Contacts. *IEEE Transactions on Device and Materials Reliability*, **2008**, 8, 272-276	1.6	7
45	In-Situ Surface Recombination Measurements of Oxygen Atoms on Anodized Aluminum in an Oxygen Plasma. *Journal of Physical Chemistry C*, **2008**, 112, 8963-8968	3.8	21
44	High Temperature Stable Contacts for GaN HEMTs and LEDs. *Materials Research Society Symposia Proceedings*, **2008**, 1108, 1		
43	Recombination probability of oxygen atoms on dynamic stainless steel surfaces in inductively coupled O2 plasmas. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2008**, 26, 455-461	2.9	19
42	Ir-based diffusion barriers for Ohmic contacts to p-GaN. *Applied Surface Science*, **2008**, 254, 4134-4138	6.7	6
41	Deep etch-induced damage during ion-assisted chemical etching of sputtered indium zinc oxide films in Ar/CH4/H2 plasmas. *Thin Solid Films*, **2008**, 516, 2869-2873	2.2	1
40	High temperature Ohmic contacts to p-type GaN for use in light emitting applications. *Physica Status Solidi C: Current Topics in Solid State Physics*, **2008**, 5, 2241-2243		
39	Effect of cryogenic temperature deposition on Au contacts to bulk, single-crystal n-type ZnO. *Applied Surface Science*, **2007**, 253, 3766-3772	6.7	17
38	Comparison of plasma chemistries for the dry etching of bulk single-crystal zinc-oxide and rf-sputtered indium zinc-oxide films. *Applied Surface Science*, **2007**, 253, 9228-9233	6.7	6
37	Improved Long-Term Thermal Stability At 350°C Of TiB2 Based Ohmic Contacts On AlGaN/GaN High Electron Mobility Transistors. *Journal of Electronic Materials*, **2007**, 36, 379-383	1.9	1
36	Effect of Cryogenic Temperature Deposition of Various Metal Contacts on Bulk Single-Crystal n-Type ZnO. *Journal of Electronic Materials*, **2007**, 36, 488-493	1.9	3
35	Annealing and Measurement Temperature Dependence of W2B- and W2B5-Based Rectifying Contacts to p-GaN. *Journal of Electronic Materials*, **2007**, 36, 384-390	1.9	7
34	Thermal Stability of Nitride-Based Diffusion Barriers for Ohmic Contacts to n-GaN. *Journal of Electronic Materials*, **2007**, 36, 1662-1668	1.9	1
33	Dry etching of zinc-oxide and indium-zinc-oxide in IBr and BI3 plasma chemistries. *Applied Surface Science*, **2007**, 253, 3773-3778	6.7	14
32	Ir/Au Ohmic Contacts on Bulk, Single-Crystal n-Type ZnO. *Journal of the Electrochemical Society*, **2007**, 154, H161	3.9	2
31	Nitride-based Ohmic and Schottky Contacts to GaN. *ECS Transactions*, **2007**, 6, 191-199	1	2
30	Ni/Au Ohmic contacts to p-type Mg-doped CuCrO2 epitaxial layers. *Applied Physics Letters*, **2007**, 90, 142104	3.4	16

29	Influence of the positive ion composition on the ion-assisted chemical etch yield of SrTiO3 films in Ar/SF6 plasmas. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2007**, 25, 425-431	2.9	6
28	Improved long-term thermal stability of InGaN/GaN multiple quantum well light-emitting diodes using TiB2- and Ir-based p-Ohmic contacts. *Applied Physics Letters*, **2007**, 90, 242103	3.4	15
27	Influence of the film properties on the plasma etching dynamics of rf-sputtered indium zinc oxide layers. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2007**, 25, 659-665	2.9	8
26	W2B and CrB2 diffusion barriers for Ni/Au contacts to p-GaN. *Applied Physics Letters*, **2007**, 91, 042105	3.4	8
25	Ohmic contacts to p-type GaN based on TaN, TiN, and ZrN. *Applied Physics Letters*, **2007**, 90, 212107	3.4	15
24	Reduction of Dry Etch Damage to GaAs Using Pulse-Time Modulated Plasmas. *Electrochemical and Solid-State Letters*, **2007**, 10, H139		1
23	Ir/Au Ohmic Contacts on Bulk, Single-Crystal n-Type ZnO. *Materials Research Society Symposia Proceedings*, **2007**, 1000, 1		
22	Ir-Based Schottky and Ohmic Contacts on n-GaN. *Journal of the Electrochemical Society*, **2007**, 154, H584	3.9	4
21	Thermal stability of Ohmic contacts to InN. *Applied Physics Letters*, **2007**, 90, 162107	3.4	7
20	Influence of redeposition on the plasma etching dynamics. *Journal of Applied Physics*, **2007**, 101, 083303	2.5	17
19	Effects of Zn content on structural and transparent conducting properties of indium-zinc oxide films grown by rf magnetron sputtering. *Journal of Vacuum Science & Technology B*, **2006**, 24, 2737		24
18	Effect of Cryogenic Temperature Deposition of Various Metal Contacts to Bulk, Single-Crystal n-type ZnO. *Materials Research Society Symposia Proceedings*, **2006**, 957, 1		
17	Schottky barrier height of boride-based rectifying contacts to p-GaN. *Applied Physics Letters*, **2006**, 89, 132110	3.4	17
16	Increased Schottky barrier heights for Au on n- and p-type GaN using cryogenic metal deposition. *Applied Physics Letters*, **2006**, 89, 122106	3.4	7
15	Influence of ion mixing on the energy dependence of the ion-assisted chemical etch rate in reactive plasmas. *Journal of Applied Physics*, **2006**, 100, 063309	2.5	9
14	High-density plasma etching of indium/zinc oxide films in Ar/Cl2 and Ar/CH4/H2 chemistries. *Applied Surface Science*, **2006**, 253, 2752-2757	6.7	12
13	Kinetics driving high-density chlorine plasmas. *Journal of Applied Physics*, **2005**, 98, 063301	2.5	16
12	Energy dependence of ion-assisted chemical etch rates in reactive plasmas. *Applied Physics Letters*, **2005**, 87, 071502	3.4	23

11	Comment on "Plasma etching of high dielectric constant materials on silicon in halogen plasma chemistries" by L. Sha and J. P. Chang [J. Vac. Sci. Technol. A 22, 88 (2004)]. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2005**, 23, 720-721	2.9	2
10	Microfabricated SrTiO3 ridge waveguides. *Applied Physics Letters*, **2005**, 86, 221106	3.4	15
9	Ion mass dependence of the etch yield of SrTiO3 films in reactive plasmas. *Applied Physics Letters*, **2005**, 87, 131503	3.4	6
8	Influence of the microstructure on the optical characteristics of SrTiO3 thin films. *Journal of Materials Research*, **2005**, 20, 68-74	2.5	8
7	Growth, Characterization and Processing of VO2 Thin Films for Micro-switching Devices. *Materials Research Society Symposia Proceedings*, **2005**, 872, 1		
6	Growth and patterning of strontium-titanate-oxide thin films for optical devices applications. *Materials Research Society Symposia Proceedings*, **2004**, 817, 141		1
5	Dependence of the sputter-etching characteristics of strontium titanate oxide thin films on their structural properties. *Applied Physics Letters*, **2004**, 84, 2500-2502	3.4	9
4	Characterization of neutral, positive, and negative species in a chlorine high-density surface-wave plasma. *Journal of Applied Physics*, **2003**, 93, 1907-1913	2.5	12
3	Barium strontium titanate etching characteristics in chlorinated discharges. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2003**, 21, 1247-1252	2.9	13
2	Sputter-etching characteristics of barium strontium titanate and bismuth strontium tantalate using a surface-wave high-density plasma reactor. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2002**, 20, 530-535	2.9	16
1	Propagation of surface waves in two-plasma systems bounded by a metallic enclosure. *Journal of Plasma Physics*, **2001**, 66, 349-362	2.7	3